

U.S. Department of Commerce, Patent and Trademark INFORMATION DISCLOSURE STATEMENT BY APPLICANT MAR 05 2004 PATENT & TRADEMARK OFFICE (Use several sheets if necessary)		Atty. Docket No.	Application No.
		TNCR.196US2	10/699,153
		Applicant(s)	Conf. No.
		Ibrahim Abdulhalim, et al.	1463
		Filing Date	Group
		October 30, 2003	1765

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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.			

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		Document	Date	Country	Class	Subclass	Yes	No

  

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		

  

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<b>Foreign Patent Documents</b>								
		Document	Date	Country	Class	Subclass	Translation	
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<b>SHEET 2 OF</b>							
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